

# Self Introduction

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- Hometown : Oita Prefecture

Usuki (1y) → Oita(16y) → Fukuoka (1y) → Kyoto(~7y)

- Hobby : Tennis、 Fishing、



@Goto Islands in Nagasaki

# Development of new High-Voltage Electrodes for Multi-gap Resistive Plate Chambers in the MARQ experiments

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**Ryotaro Koike**  
Kyoto University

- **MARQ experiments**

Collection of experiments at the J-PARC  $\pi 20$  beamline ( $\pi, K, p$  up to 20 GeV/c) such as Charmed baryon spectroscopy, Xi baryon spectroscopy, and  $I = 3$  dibaryon search.

- **MARQ spectrometer**

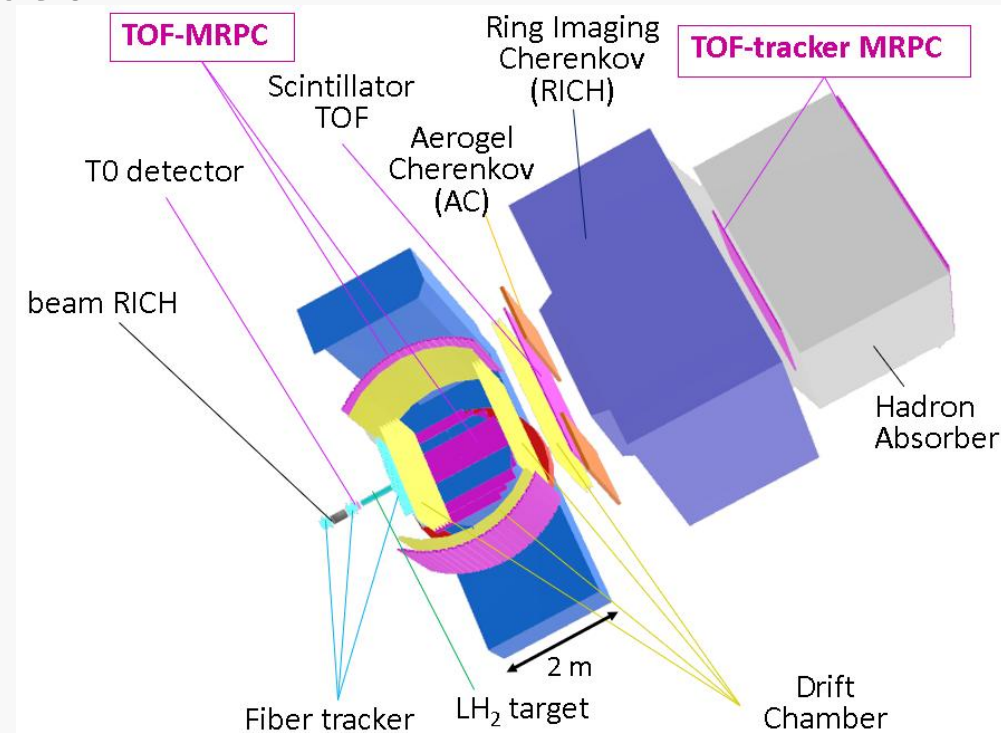
A versatile spectrometer which performs particle identification even at momenta of 20 GeV/c with a great momentum resolution in a high intensity situation

## Multi-gap Resistive Plate Chamber(MRPC)

serves as a stop timing detector of TOF system in the MARQ spectrometer.

- **Desired Performance of MRPC**

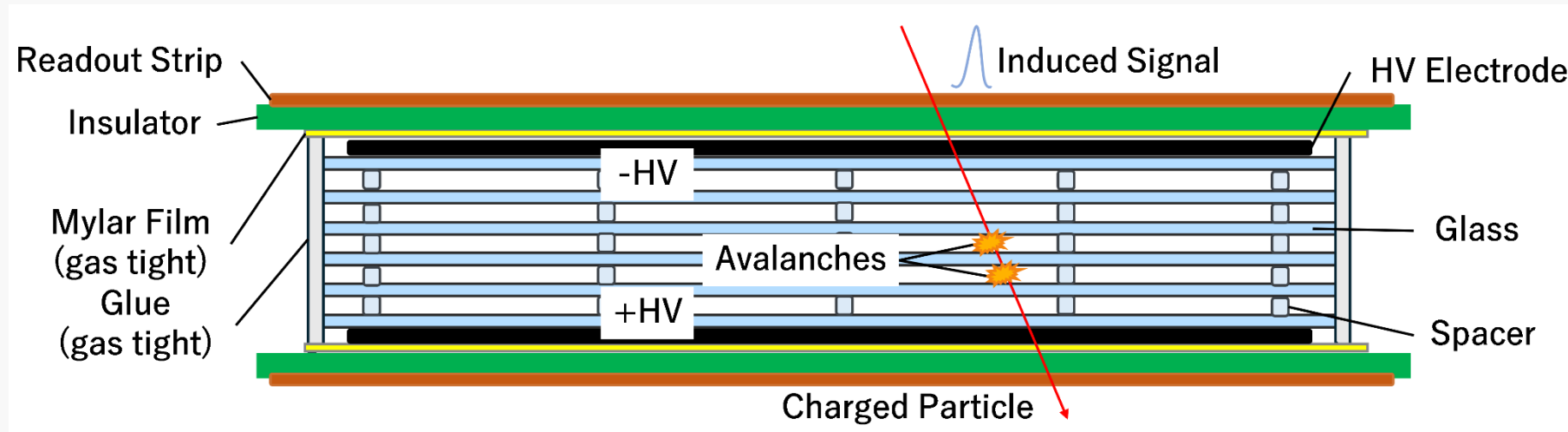
- Total Coverage: 11 m<sup>2</sup>
- Time Resolution: ~60 ps
- Efficiency: 99 %



# Multi-gap Resistive Plate Chamber (MRPC)

- MRPC ... gaseous detector for charged particles

Electron avalanches  $\Rightarrow$  Electric distortions in gas gaps  $\Rightarrow$  Induce signals on readout strips



- Roles of HV electrode

- Creates a uniform electric field
- Prevents the induced charge from dispersing

$\Rightarrow$  standard resistivity :  $10^5 \sim 10^7 \Omega/\text{cm}^2$

if it's too low ... Low performance due to charge sharing between strips

too high ... Voltage drop along the HV electrodes, causing non-uniform fields

- **Problems of former HV electrode (T-9188 from the EEEEC company)**
  - Adhesive, high-resistivity tape
  - Different resistivities for different lots
  - **Discontinued**, causing MRPC developments in Japan difficult

⇒ **Purpose:**

To find alternative HV electrodes and make MRPC development possible

- **Requirements for HV electrodes**
  - Work as HV electrodes for MRPC (i.e., HV suppliable and signals readable)
  - Stable operation with large MRPC (MRPC for MARQ experiments will be 1.8 m long)
  - Uniform Resistivity
  
  - (mass-productivity)
  - (stable resistivity, resistivity reproducible, stable supply)

## No promising candidates so far

- First, we looked for high-resistivity adhesive tapes. (2020 Mater thesis from Tohoku Univ.) Found one candidate (MK-APT from Tanimura company), but stability issue.
- We also considered coatings which are used in foreign groups, but faced problems of imports, maximum size, coating methods, etc.

## This work focused on new conductive coatings

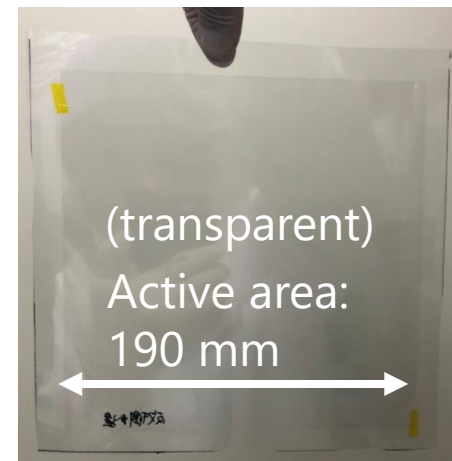
### Coatings on Glass

- HV electrode and Glass is well attached
- Simple assemble procedure
- Risk of damaging the glass while coating
- Varying quality due to hand coating



### Coatings on Film

- Produce HV electrodes separately from glass
- Minimum risk of damage
- Great mass-producibility by machine coating
- Reproducible and even quality

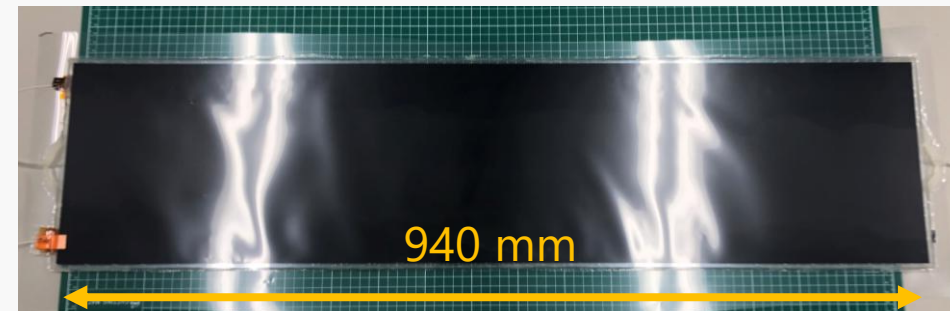


# List of new candidates

- **Seplegyda from Shinetsu Polymer (Japan)**
  - Polythiophene-base conductive polymer (intrinsically conductive polymer)
  - Applications: antistatic on packing sheet for IC, display
- **Air-Opaque from Badger Air-Brush**
  - Colloidal graphite gives conductivity
  - Water-based ink for illustrators
  - adopted in SHiP experiment
- **Graphit from Kontakt Chemie**
  - Colloidal graphite gives conductivity
  - Conductive coating used for electronics mainly in Europe
  - adopted in Lyon university
- **CS-6301 / CS-5302 from Colcoat (Japan)**
  - Nano carbon dispersed polysiloxane
  - Antistatic application
- **KP-8348-1 / KP-K2919-1 from Kansai-Polymer (Japan)**
  - Fluoropolymer-base carbon dispersed conductive coating
  - Applications: antistatic in semiconductor region

## Assembled prototype MRPCs using new HV electrodes

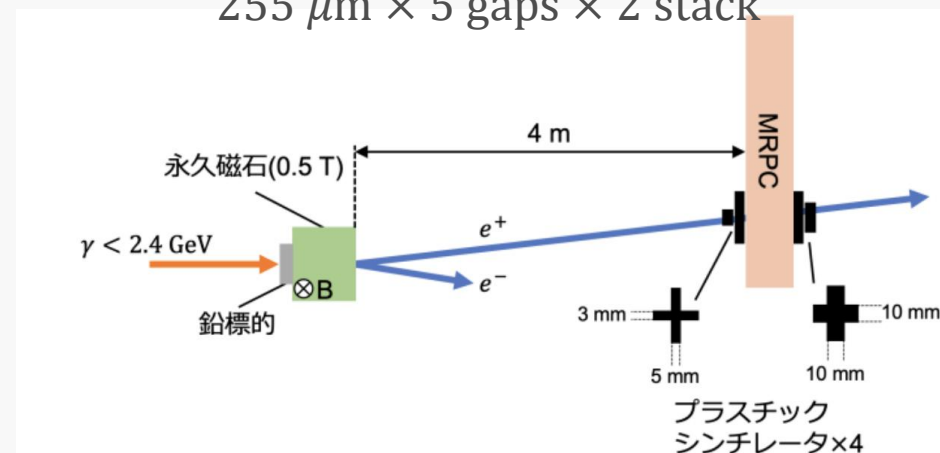
- asked companies to apply the coatings
- fabricated prototypes in our laboratory
- started with small size(20 cm sq.),  
and then made the succussed ones larger (~1 m long)



## Evaluated the performance using an electron beam

- SPring-8 LEPS2 beamline
- $e^-/e^+$  of  $\sim 1$  GeV/c momenta
- Checked whether the chamber is working based on efficiency and time resolution

Gas gap configuration :  
 $255 \mu\text{m} \times 5 \text{ gaps} \times 2 \text{ stack}$



## ● Evaluation method

- Efficiency:  $(N_{\text{MRPC\_hits}} / N_{\text{trigger}})$
- Time Resolution: standard deviation of  $(T_{\text{MRPC}} - T_{\text{RF}})$ ,  
where  $T_{\text{MRPC}}$  is the mean timing of signals from the left end and right of a strip,  
and  $T_{\text{RF}}$  is the timing of RF signal, which is synchronized with the beam bunch.



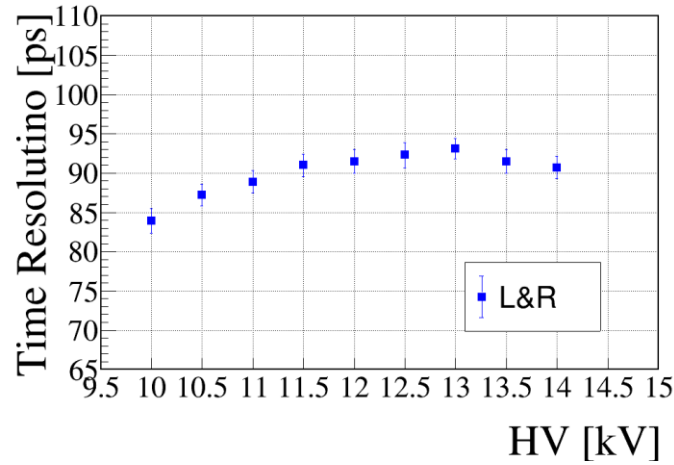
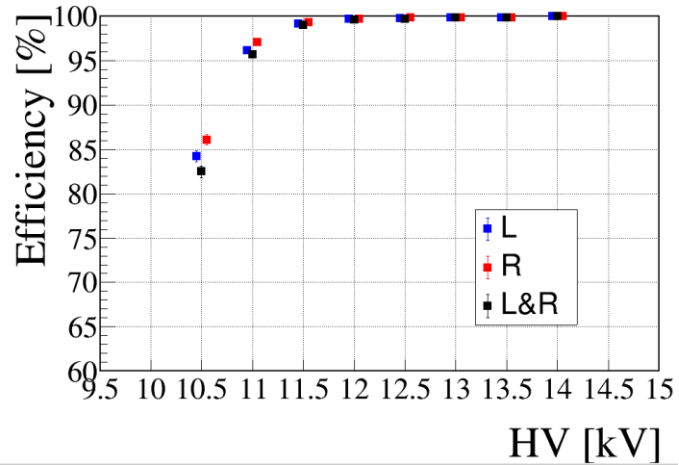
Coating	substrate	technic	resistivity	CR test	1st beam test	2nd beam test
Seplegyda	Film	barcoater	$\sim 6 \times 10^5 \Omega/\text{cm}^2$	×	-	-
Air-Opaque	Film	barcoater	$\sim 5 \times 10^{10} \Omega/\text{cm}^2$	×	-	-
① Graphit 33	Film	paint roller	$\sim 2 \times 10^6 \Omega/\text{cm}^2$	○	conducted	-
② CS-6301 (1)	Glass	hand spray	$\sim 4 \times 10^6 \Omega/\text{cm}^2$	○	conducted	-
③ CS-6301 (2)	Film	microgravure	$\sim 3 \times 10^6 \Omega/\text{cm}^2$	○	conducted	conducted
④ CS-5302	Film	microgravure	$\sim 2 \times 10^4 \Omega/\text{cm}^2$	○	-	conducted
⑤ KP-8348-1	Glass	hand spray	$\sim 2 \times 10^4 \Omega/\text{cm}^2$	○	conducted	conducted
⑥ KP-K2919-1	Film	hand spray	$\sim 2 \times 10^8 \Omega/\text{cm}^2$	○	-	conducted

- **Seplegyda : dark currents ×**  
Due to intrinsically conductive coating?
- **Air-Opaque : dark currents ×**  
Difficulties in getting desired resistivity
- **Others: passed CR test in laboratory, and proceed to the beam tests**

Coating	substrate	technic	resistivity	CR test	1st beam test	2nd beam test
Seplegyda	Film	barcoater	$\sim 6 \times 10^5 \Omega/\text{cm}^2$	×	-	-
Air-Opaque	Film	barcoater	$\sim 5 \times 10^{10} \Omega/\text{cm}^2$	×	-	-
① Graphit 33	Film	paint roller	$\sim 2 \times 10^6 \Omega/\text{cm}^2$	○	conducted	-
② CS-6301 (1)	Glass	hand spray	$\sim 4 \times 10^6 \Omega/\text{cm}^2$	○	conducted	-
③ CS-6301 (2)	Film	microgravure	$\sim 3 \times 10^6 \Omega/\text{cm}^2$	○	conducted	conducted
④ CS-5302	Film	microgravure	$\sim 2 \times 10^4 \Omega/\text{cm}^2$	○	-	conducted
⑤ KP-8348-1	Glass	hand spray	$\sim 2 \times 10^4 \Omega/\text{cm}^2$	○	conducted	conducted
⑥ KP-K2919-1	Film	hand spray	$\sim 2 \times 10^8 \Omega/\text{cm}^2$	○	-	conducted

- CS series (③ and ④) and KP series (⑤ and ⑥) were tested using large prototypes, based on the results of the first beam test
- Stopped trying ① Graphit 33 because it has a problem with import
- Only the results of ⑤ KP-8348-1 will be shown in this talk.

## Performance on a strip (⑤KP-8348-1)

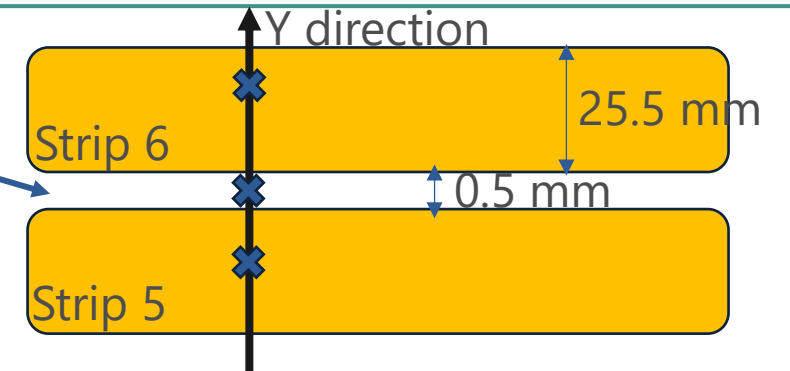
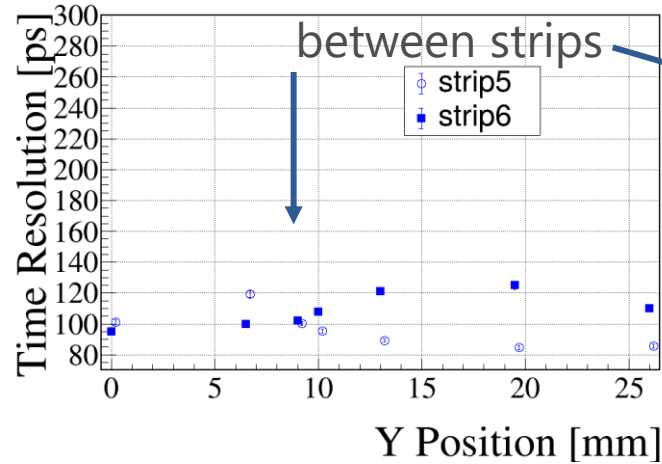
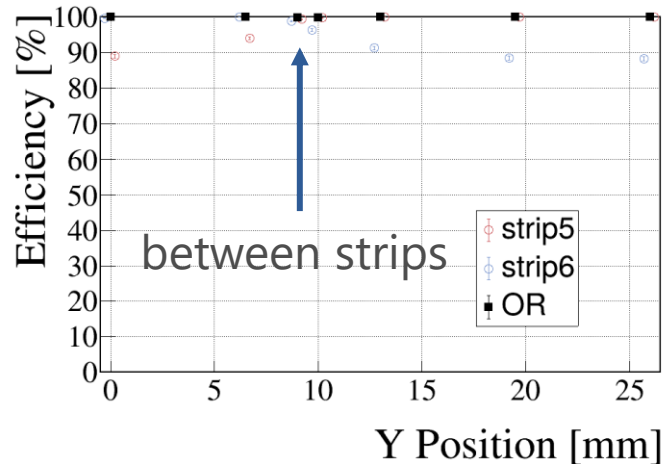


HV scan at the top of a strip

Efficiency: 99+ %

Time Resolution: ~ 90 ps

## Performance between strips (⑤KP-8348-1)



Efficiency (OR): 99+ %

Time Resolution ~ 100 ps

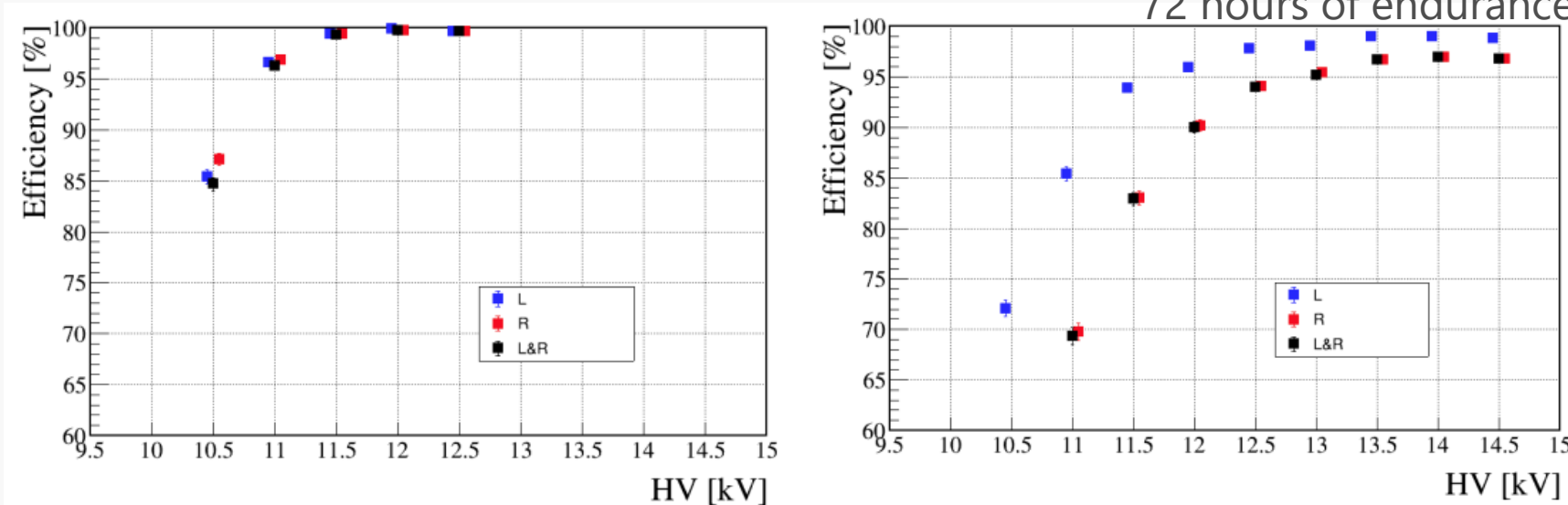
- ⑤ KP-8348-1 showed reasonable performances even with a ~1 m prototype.

- Reasonable performances confirmed for all the other candidates too

However... shifts of plateau curve were seen for both CS series

(probably 1 electrode among 4 was electrically detached)

although there was no problem after 72 hours of endurance test in the lab.



Plateau curve of ④ CS-5302 (before / after)

Chamber	on a strip	between strips	stability	producibility	reproducibility
③ CS-6301 (on Film)	99.6 %, 77.8 ps	95+ %, 100–140 ps	△	○	○
④ CS-5302 (on Film)	99.4 %, 70–80 ps	99.1 %, 85.8 ps	△	○	○
⑤ KP-8348-1	99.9 %, ~ 100 ps	99.9 %, 101.0 ps	○	△	△
⑥ KP-K2919-1	~ 80 %, ~ 100 ps	~ 80 %, 120–180 ps	○	△	?

We explored an alternative new HV electrodes for MRPC detector

**Multiple candidates** eventually are found;

- ③ CS-6301 / ④ CS-5302
    - 99 % efficiency, ~70 ps time resolution at best.
    - Coating on a film enables us to produce a large quantity with desired resistivity.
    - Issues with stability, which may come from assembling process of MRPC.
  - ⑤ KP-8348-1
    - 99 % efficiency, ~100 ps time resolution.
    - Hand coating resulted in high risk of glass breaking, high cost of mass production, and low reproducibility in resistivity.
    - The operation was very stable.
- ⇒ CS series if the stability issues are resolved

**To do**

- To find the reason why CS series broke and fix it.
- Optimization of resistivity.

# Backup

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# Effects of time resolution to PID

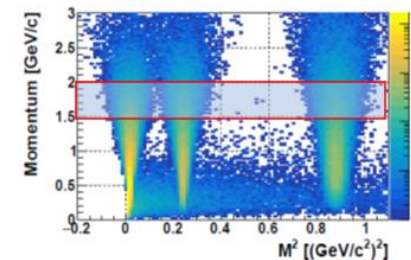
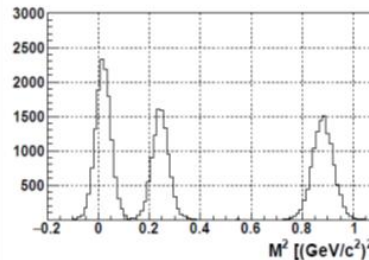
- TOF time resolution affects the resolution of mass squared
  - affects the fraction of events in which particles are identified
  - Start counter is already developed ( $\Delta T \sim 40$  ps)

## ITOF PID performance: $1.5 < p < 2.0$ GeV/c

simulation

4

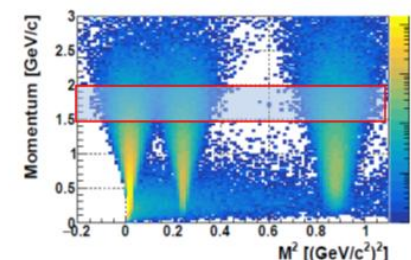
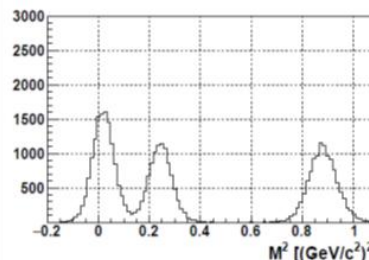
$\Delta T_{TOF} = 50$  ps (rms)



ITOF requirements

- Up to 2 GeV/c
- ⇒ Vth AC: > 2.5 GeV/c
- $\Delta T = \sim 60$  ps(rms)

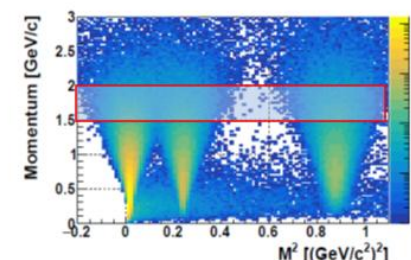
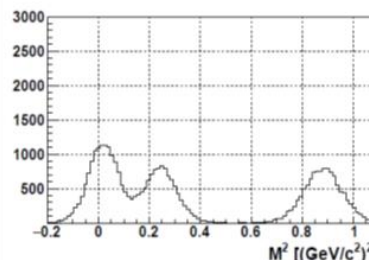
$\Delta T_{TOF} = 70$  ps (rms)



If  $\Delta T_{MRPC} \sim 60$  ps →

$1.5 < p < \dots$

$\Delta T_{TOF} = 100$  ps (rms)



If  $\Delta T_{MRPC} \sim 90$  ps →

$M^2 = (p/\beta)^2(1-\beta^2)$  distribution.

Charge is not distinguished.

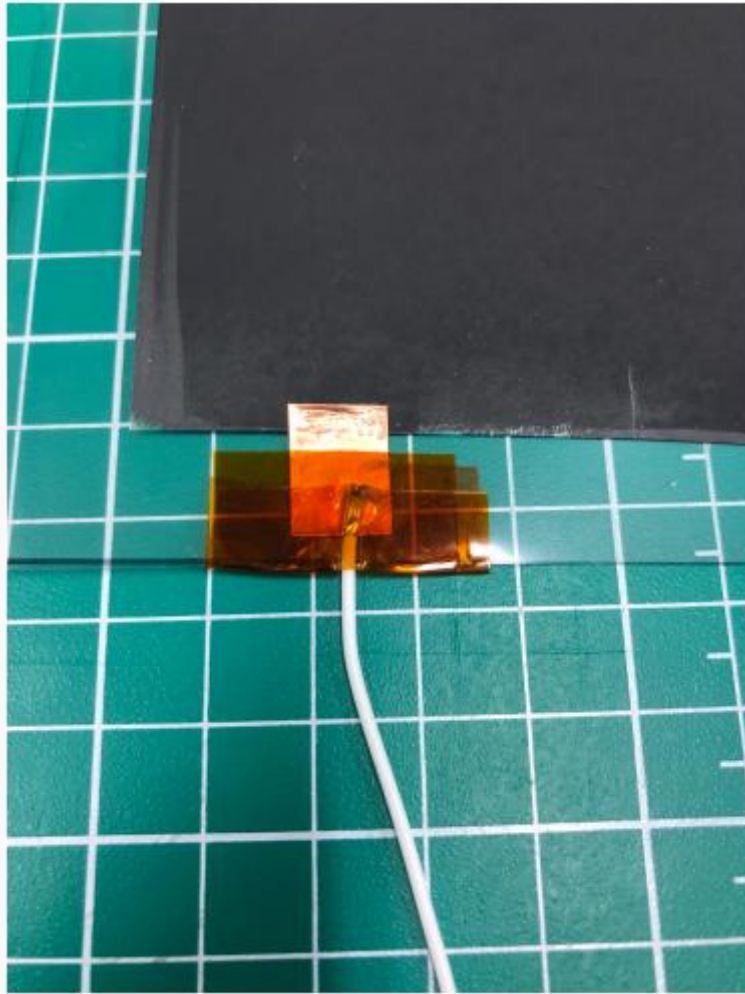
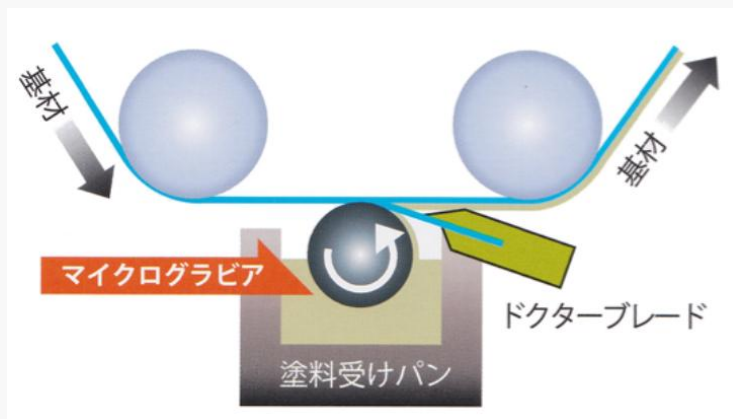


Image of HV connecting point



- Microgravure



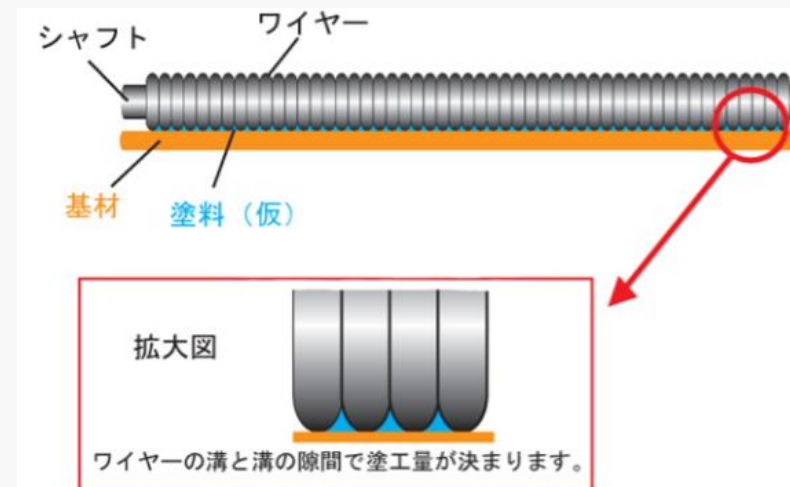
<https://www.labojapan.co.jp/labotech/coating/#micro>

- Hand spray



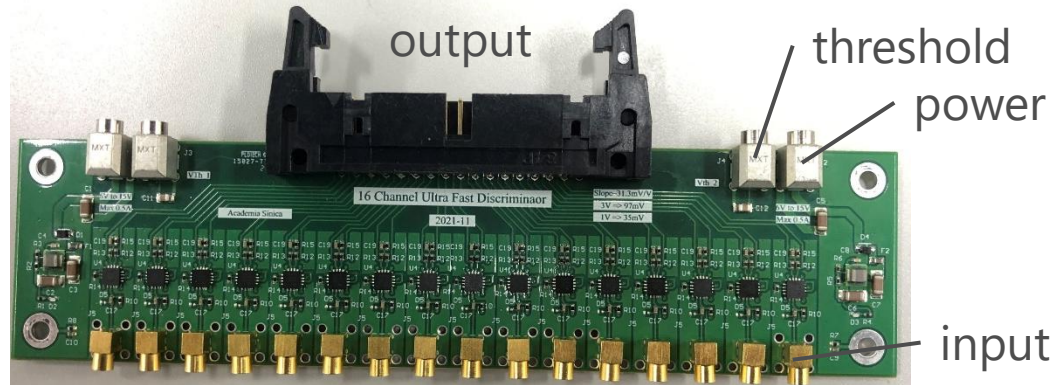
<https://kansaipolymer.co.jp/strength/method>

- Barcoater



<https://www.mitsuiec.co.jp/Wirebar>

## Discriminators (Academia Sinica)

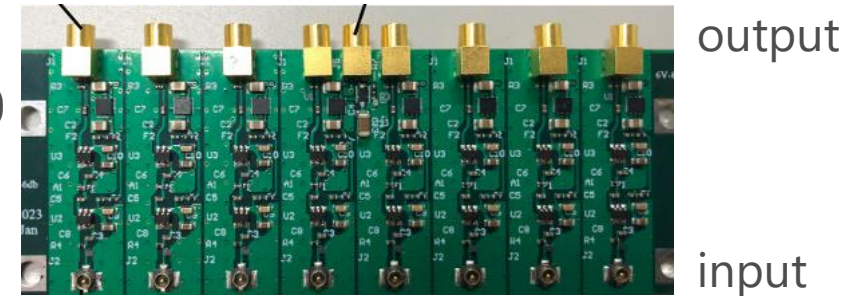


**Width-varying output** depending on the input width

## Amplifiers (Academia Sinica)

fast.

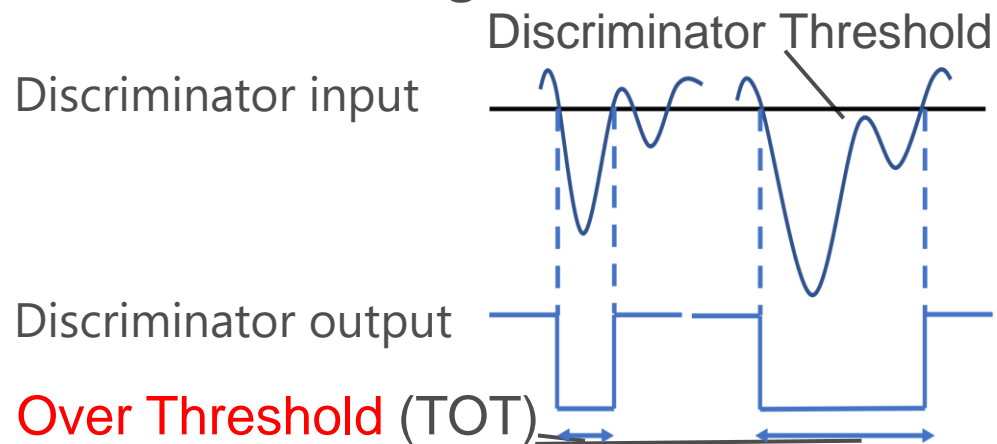
gain :  $\times \sim 300$



## Time Over Threshold (TOT)

Width of the discriminator output.

A representative of charge.



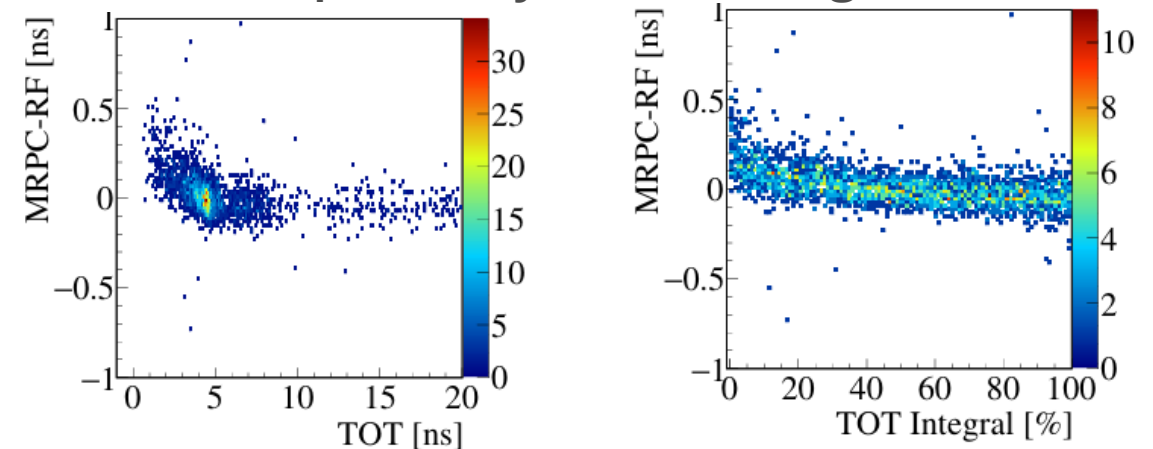
**Time Over Threshold (TOT)**

## Slewing correction with TOT integral

A slew. corr. method that can be done only with TDC.

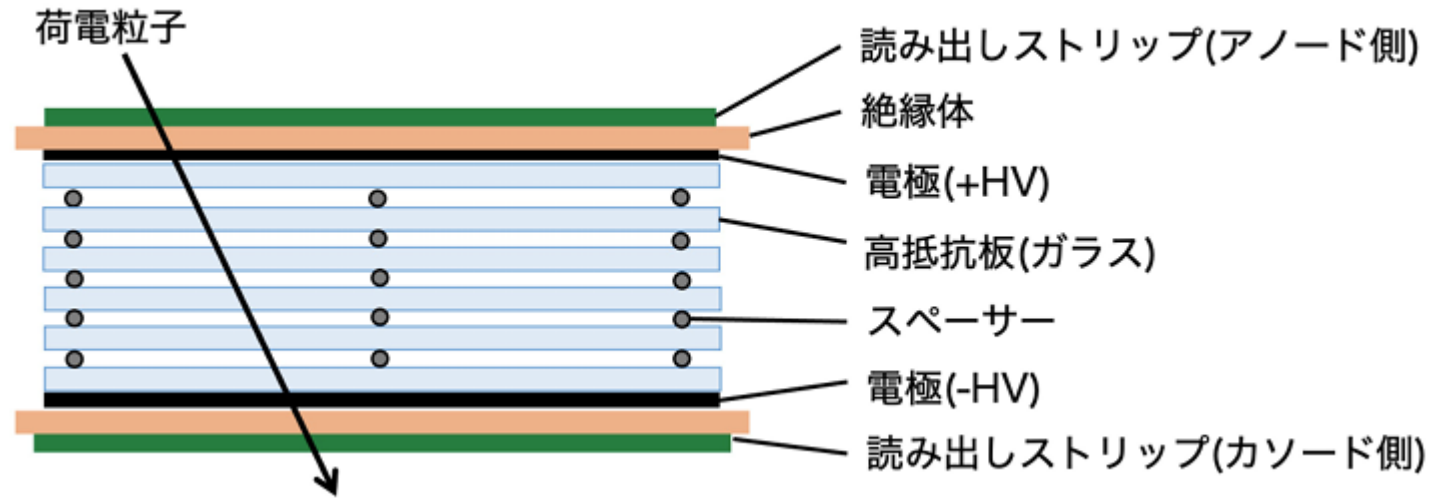
TOT integral = percentile of a tot in a tot distribution

Subtract the dependency on TOT integral

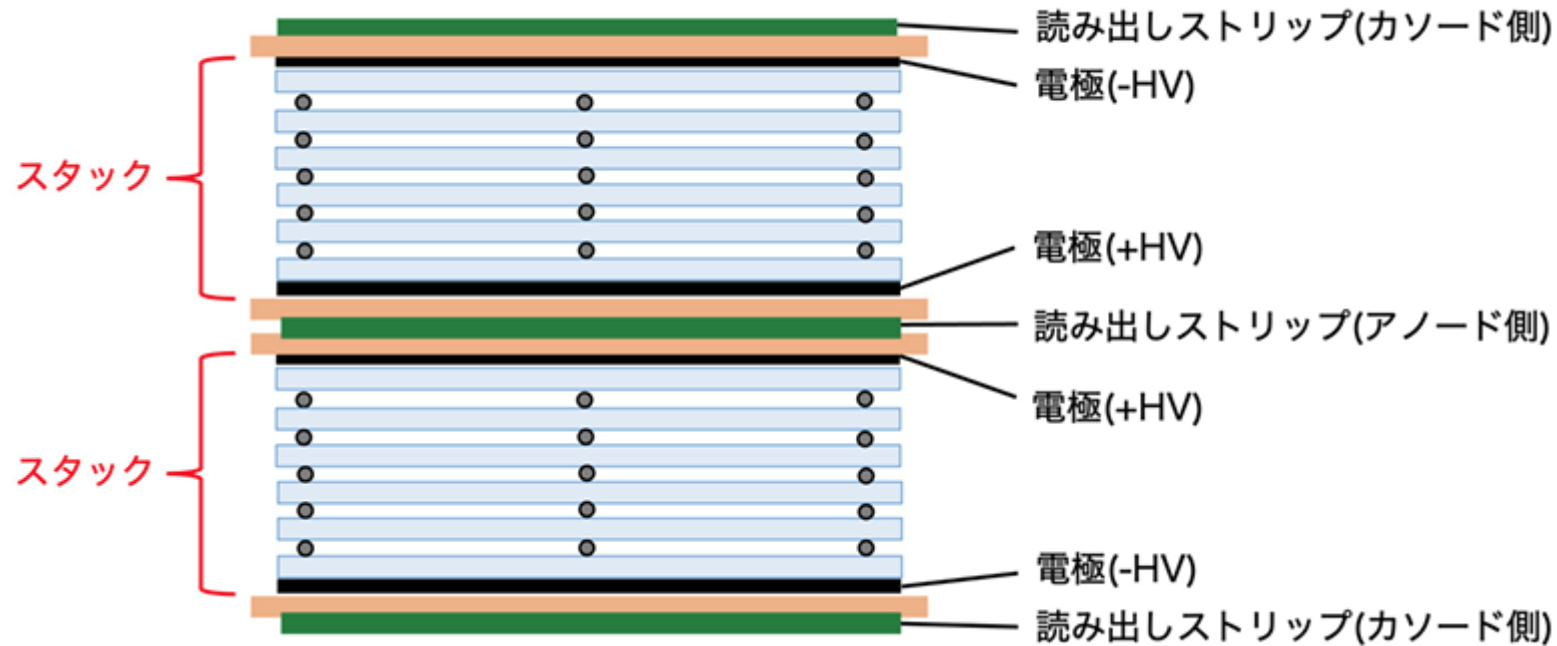


# 1 stack MRPC と 2 stack MRPC

1 stack MRPC



2 stack MRPC



Small (200 mm × 200 mm) prototypes for 1<sup>st</sup> beamtest

塗料	塗布形態	抵抗率	Gas gap configuration
Air-Opaque	フィルム塗布	$5 \times 10^{10} \Omega/\text{cm}^2$	255 $\mu\text{m}$ × 5 gap × 1 stack
Graphit 33	フィルム塗布	$2 \times 10^6 \Omega/\text{cm}^2$	255 $\mu\text{m}$ × 5 gap × 1 stack
KP-8348-1	ガラス塗布	$2 \times 10^4 \Omega/\text{cm}^2$	255 $\mu\text{m}$ × 5 gap × 1 stack
CS-6301 (1)	ガラス塗布	$4 \times 10^6 \Omega/\text{cm}^2$	255 $\mu\text{m}$ × 5 gap × 1 stack
CS-6301 (2)	フィルム塗布	$3 \times 10^6 \Omega/\text{cm}^2$	255 $\mu\text{m}$ × 5 gap × 1 stack
セプルジータ	フィルム塗布	$6 \times 10^5 \Omega/\text{cm}^2$	255 $\mu\text{m}$ × 5 gap × 1 stack

Large (~1 m long) prototypes for 1<sup>st</sup> beamtest

電極	塗布形態	塗布方法	Glass size	stack	率
CS-6301	フィルム塗布	マイクログラビア	940 mm × 230 mm	2 stack	$\sim 1 \times 10^6 \Omega/\text{cm}^2$
CS-5302	フィルム塗布	マイクログラビア	870 mm × 230 mm	2 stack	$\sim 2 \times 10^4 \Omega/\text{cm}^2$
KP-8348-1	ガラス塗布	スプレーガン	940 mm × 230 mm	2 stack	$\sim 2 \times 10^4 \Omega/\text{cm}^2$
KP-K2919-1	フィルム塗布	スプレーガン	200 mm × 200 mm	1 stack	$\sim 2 \times 10^8 \Omega/\text{cm}^2$

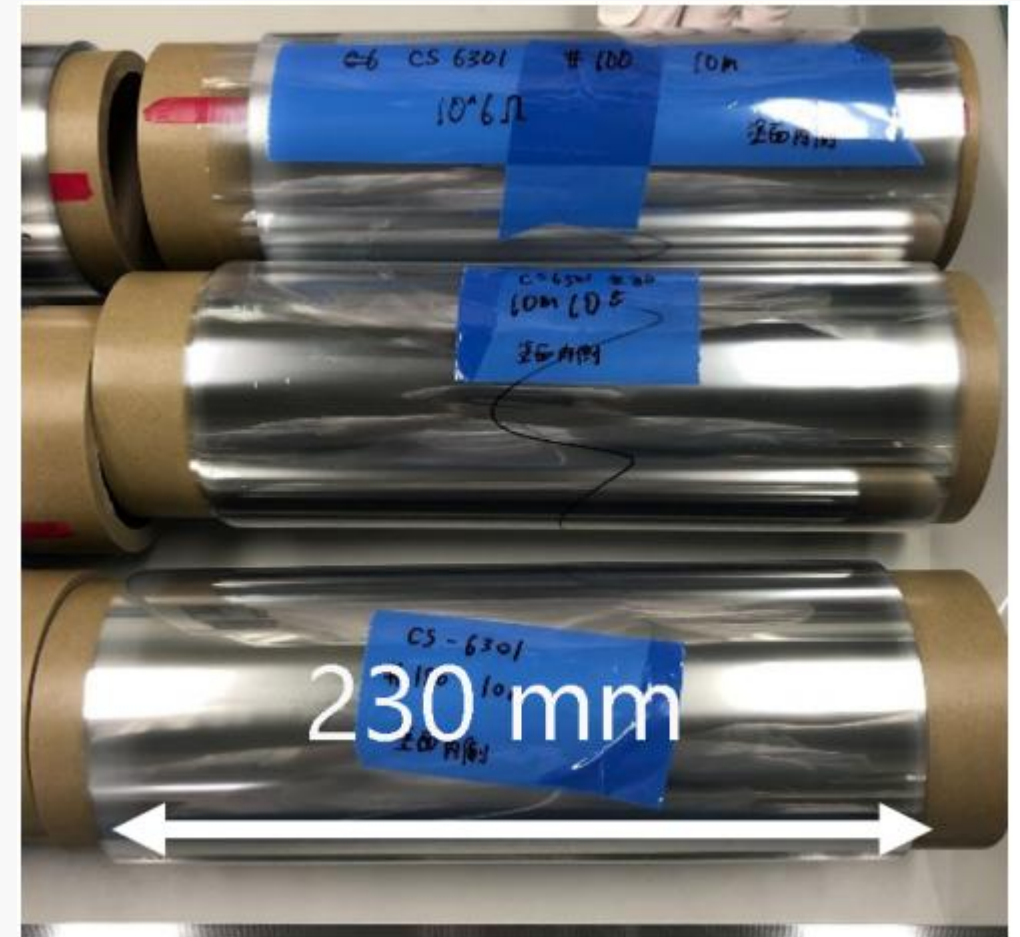
(注) Gas gap configuration per stack is **260  $\mu\text{m}$  × 5 gaps** である。)

# Adjustment of resistivity

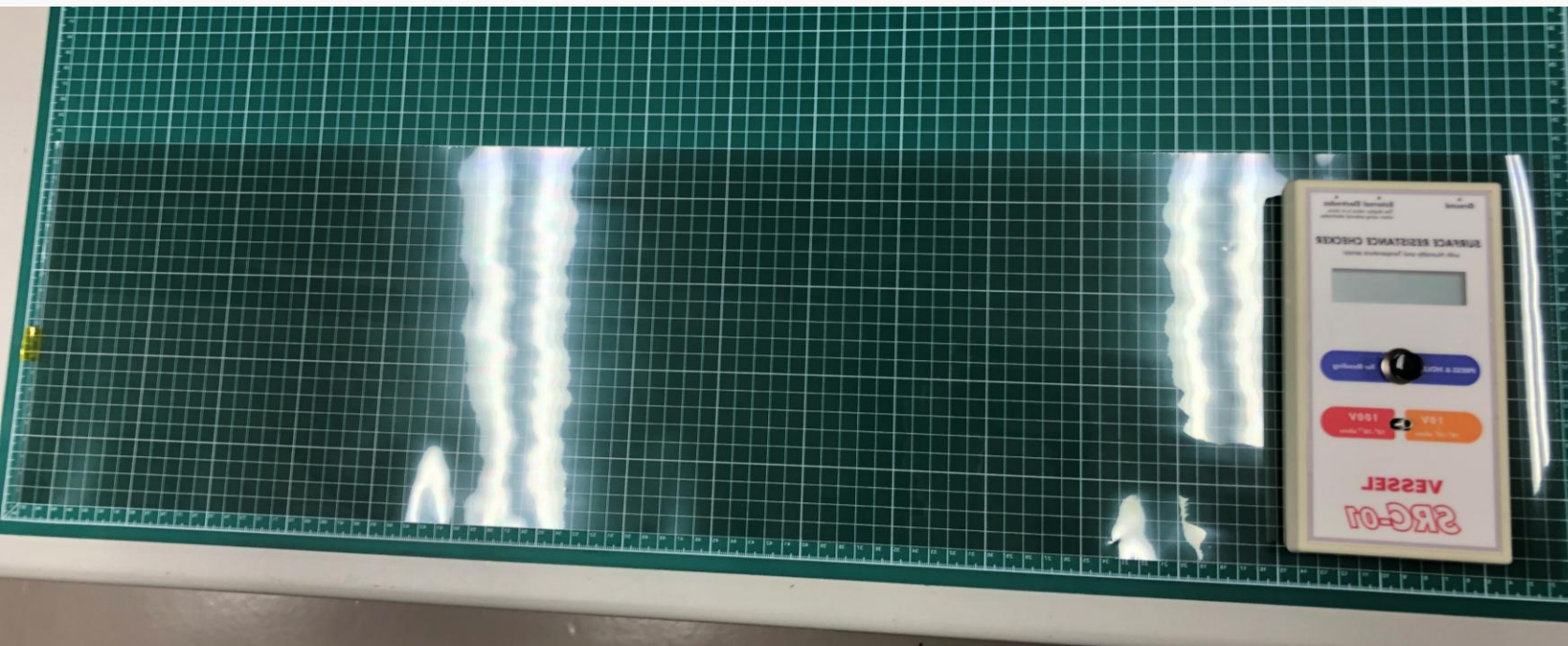
We can adjust various resistivity using CS-6301 by changing the thickness of coating.

We made several sample and confirmed the resistivity shown below can be achieved.

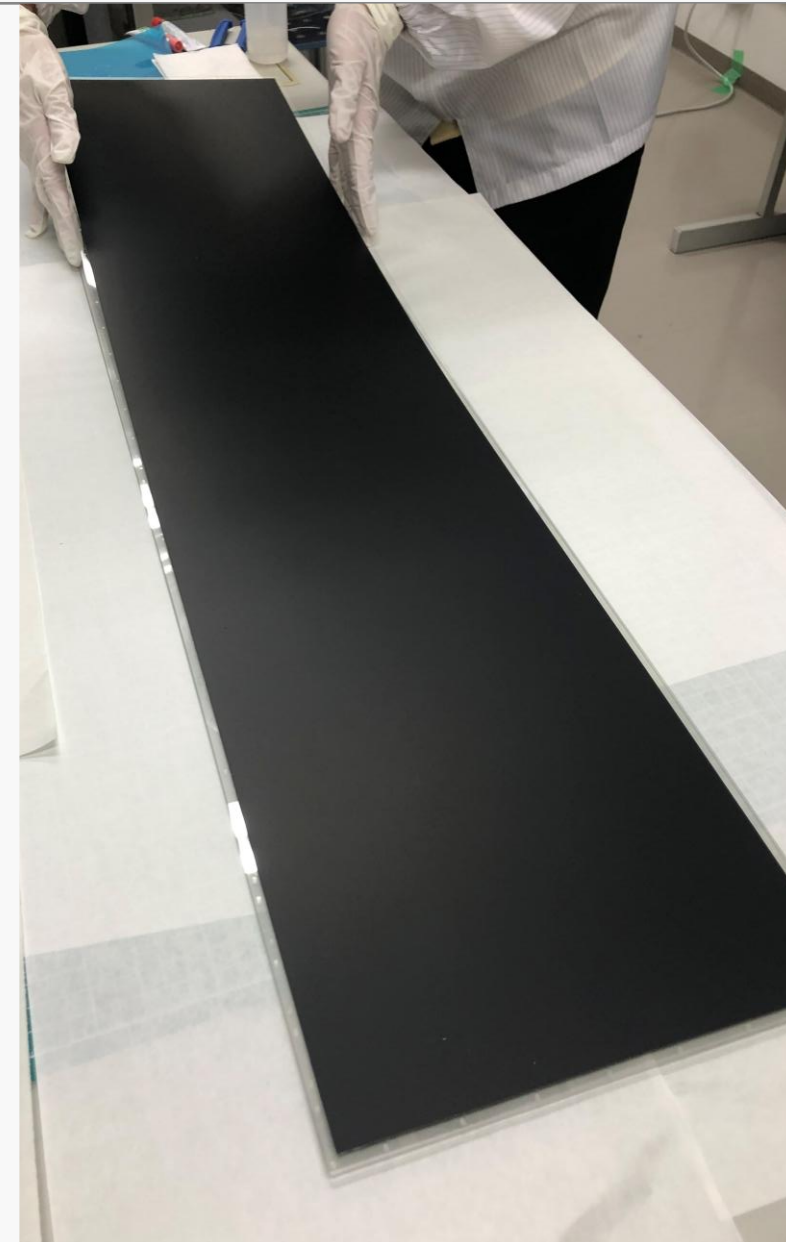
- CS-6301 :  $10^5$ ,  $10^6$ ,  $10^7$   $\Omega$ /sq.
- CS-5302 :  $10^4$ ,  $10^5$ ,  $10^8$   $\Omega$ /sq.



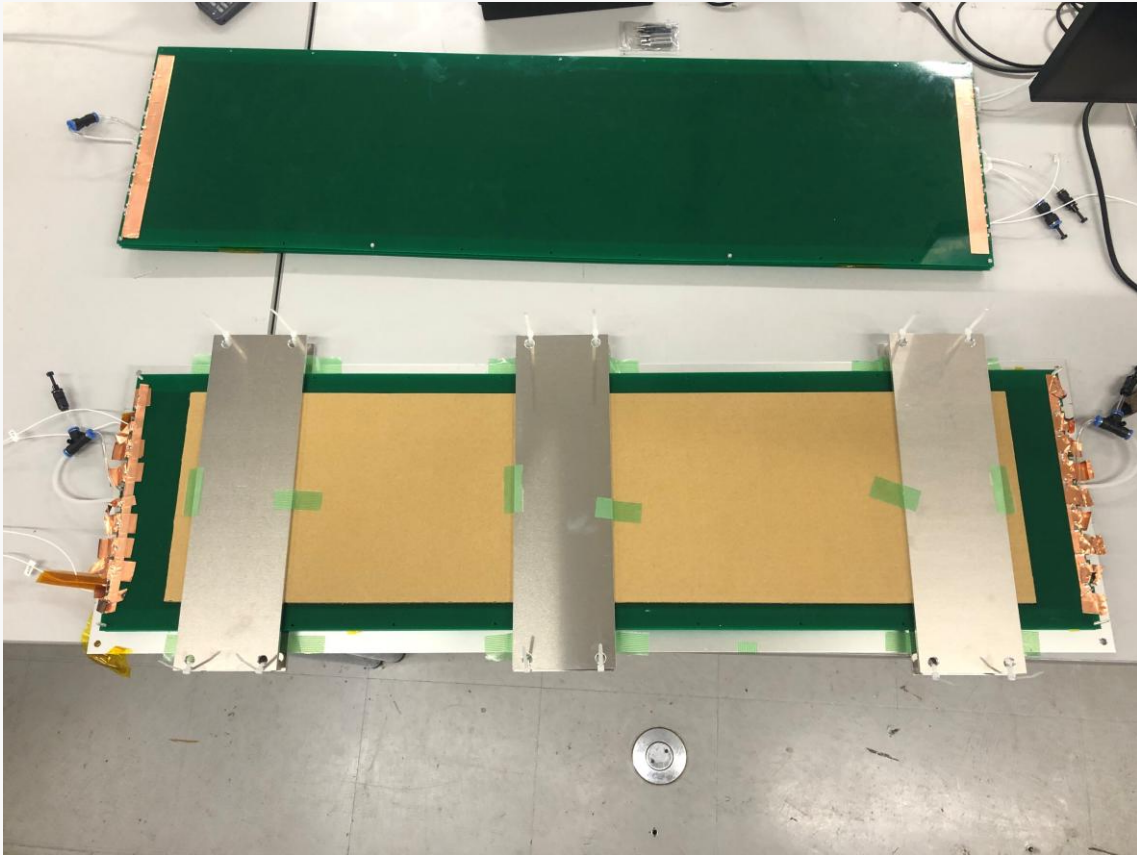
Rolls of film coated with CS-6301



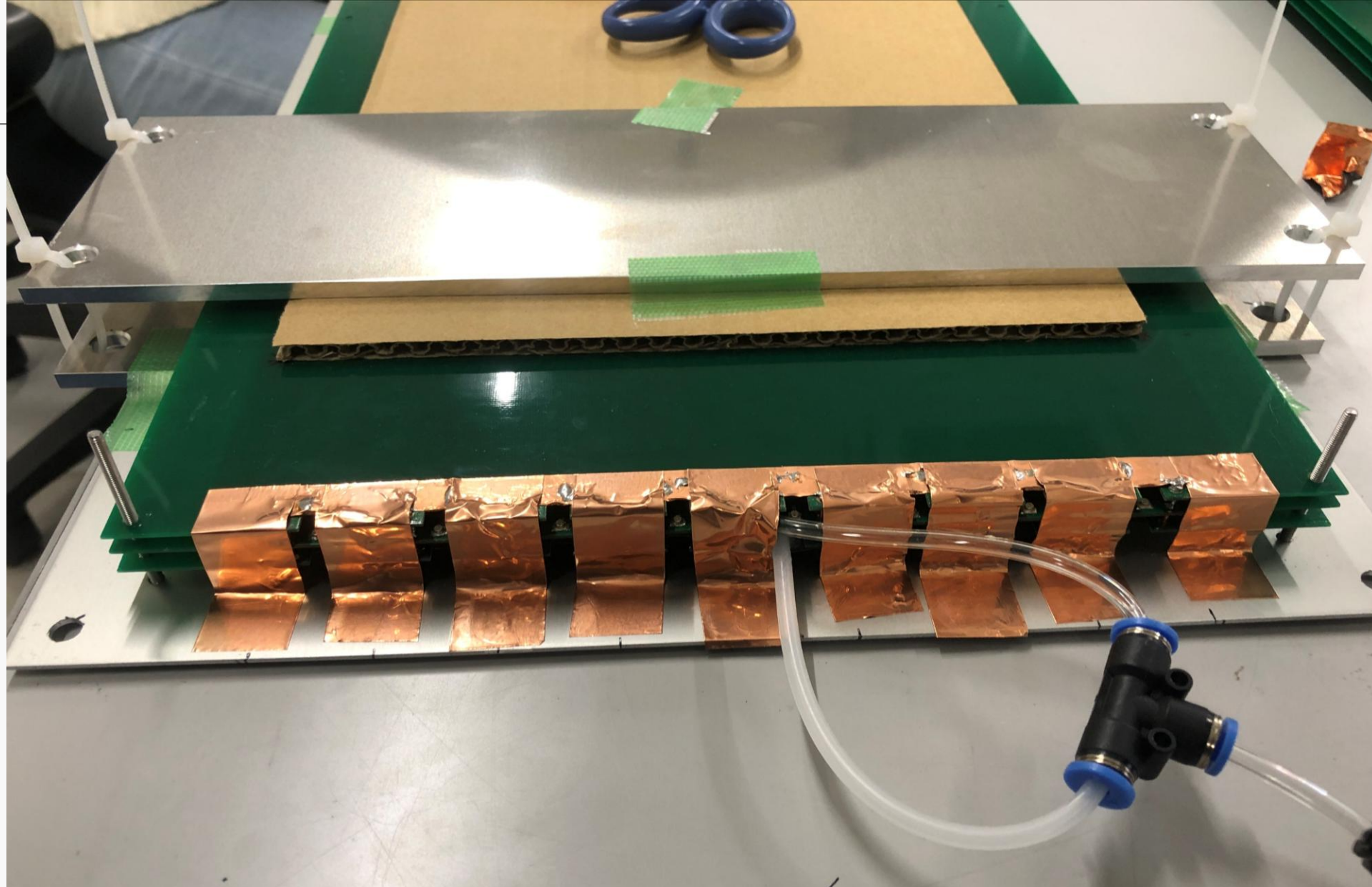
④CS-5302



⑤KP-8348-1



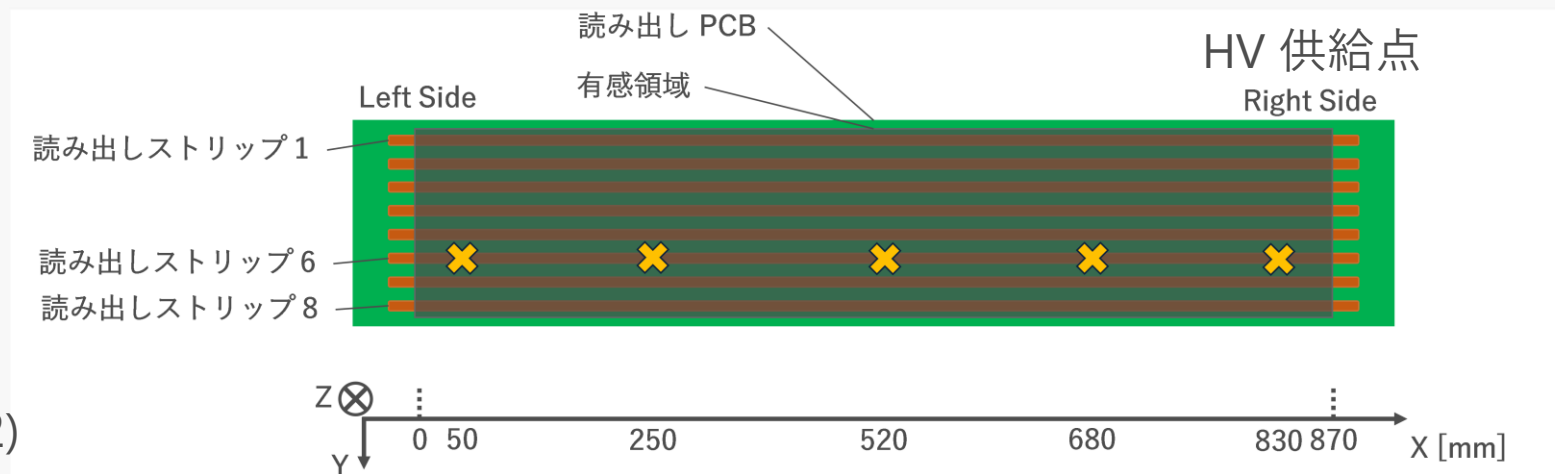
Electric contact was assured by pressing



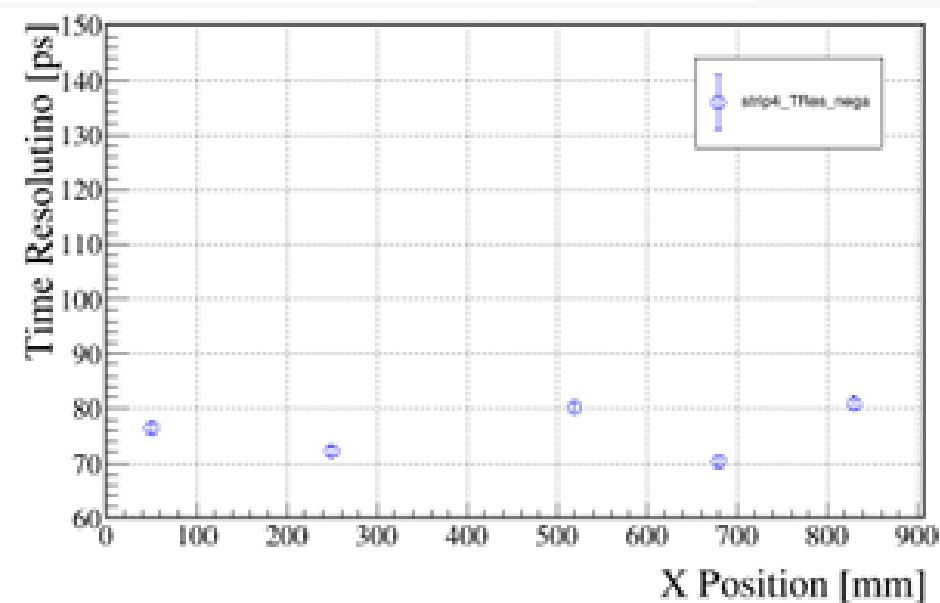
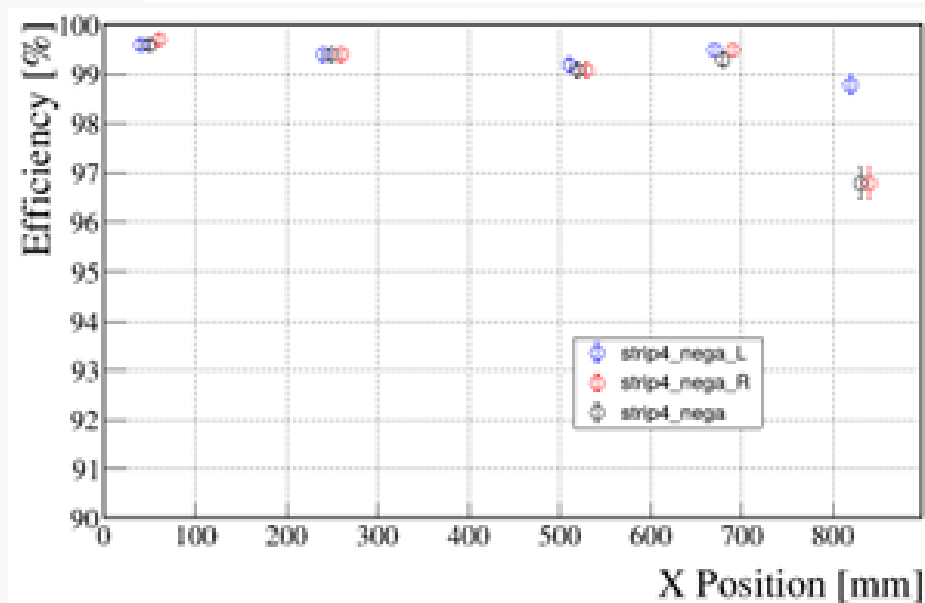
Grounding for noise reduction



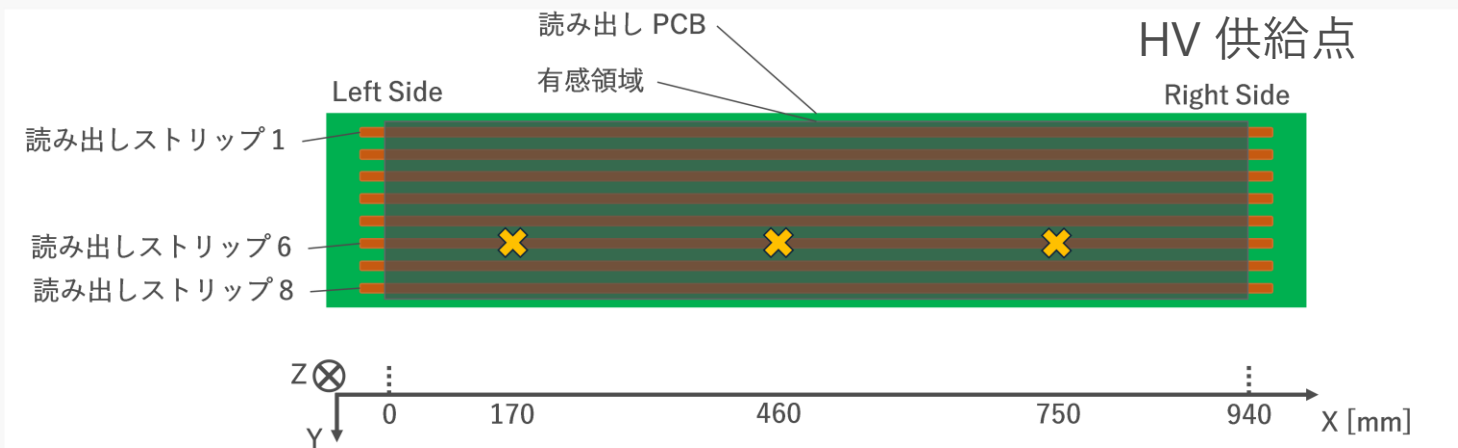
- 電圧降下の兆候もなかった



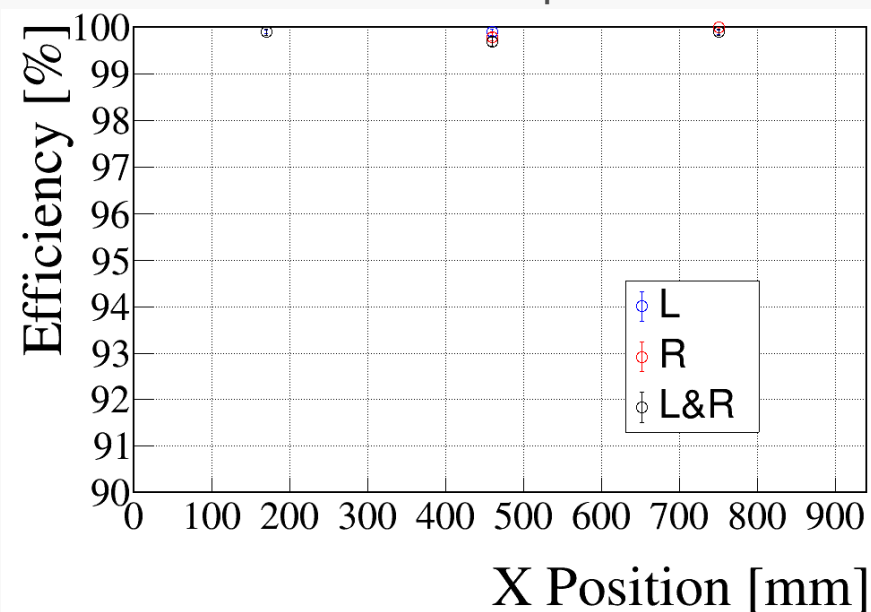
X position scan の結果 (④ CS-5302)



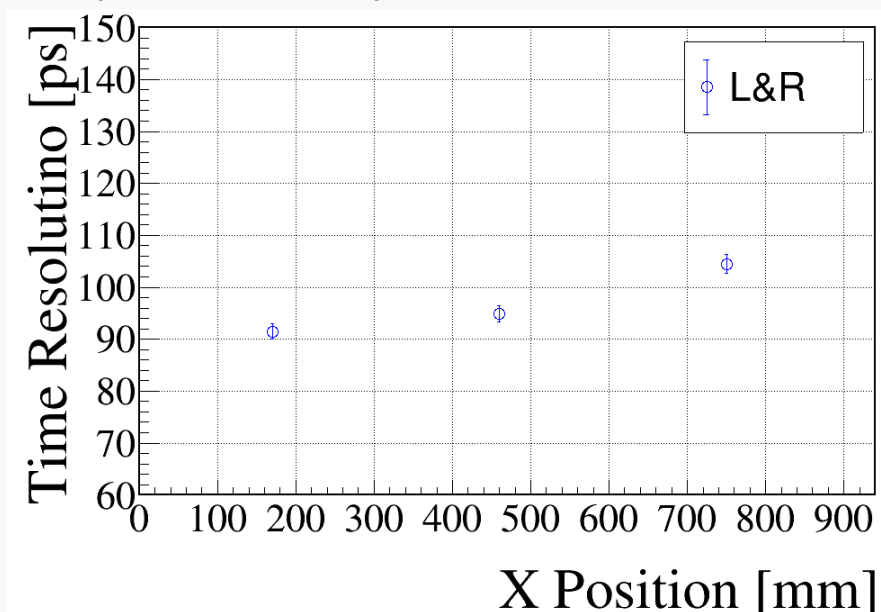
## ● 電圧降下の兆候もなかった

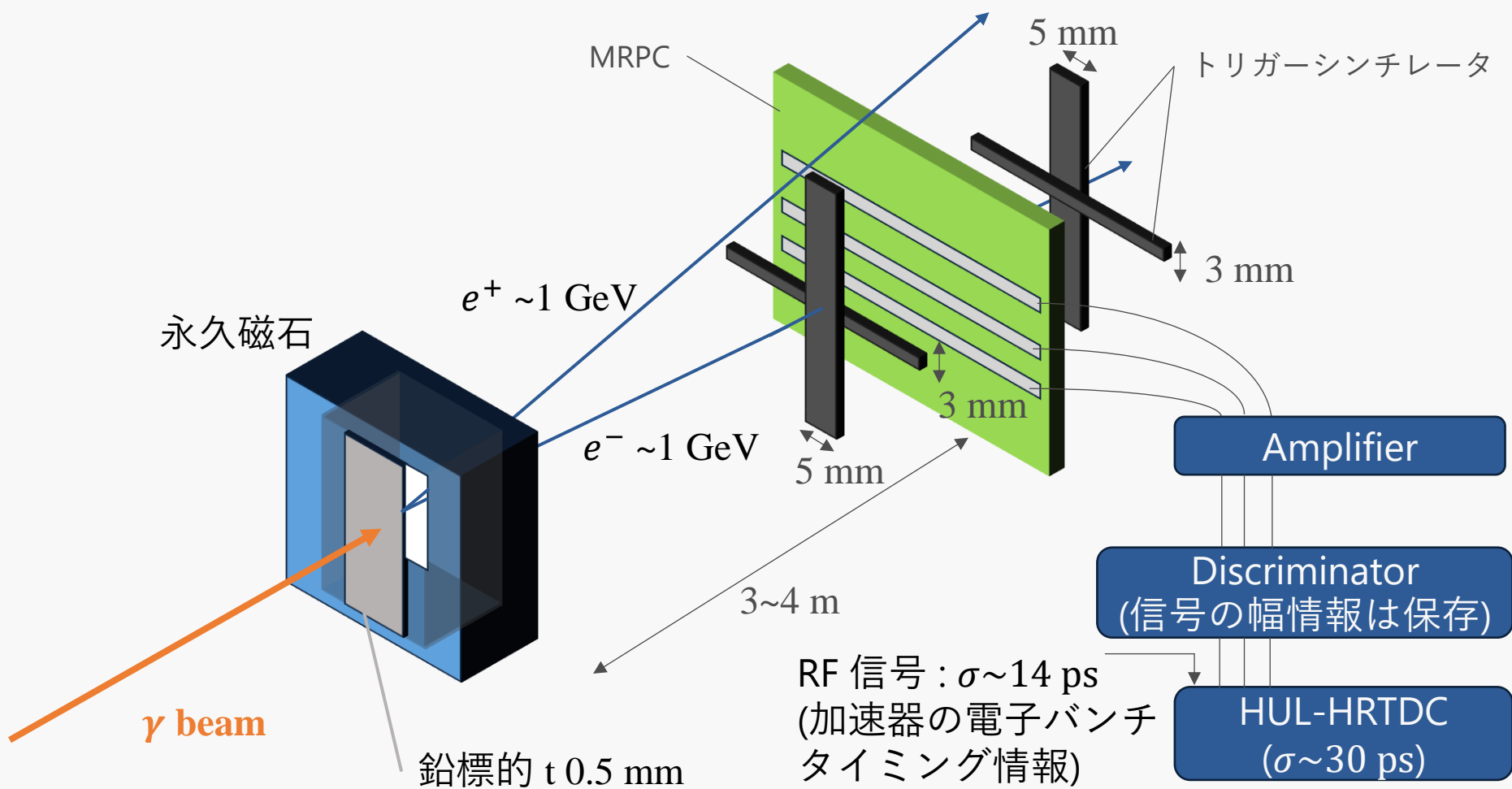


X position scan の結果 (⑤ KP-8348-1)



X position scan の結果 (⑤ KP-8348-1)





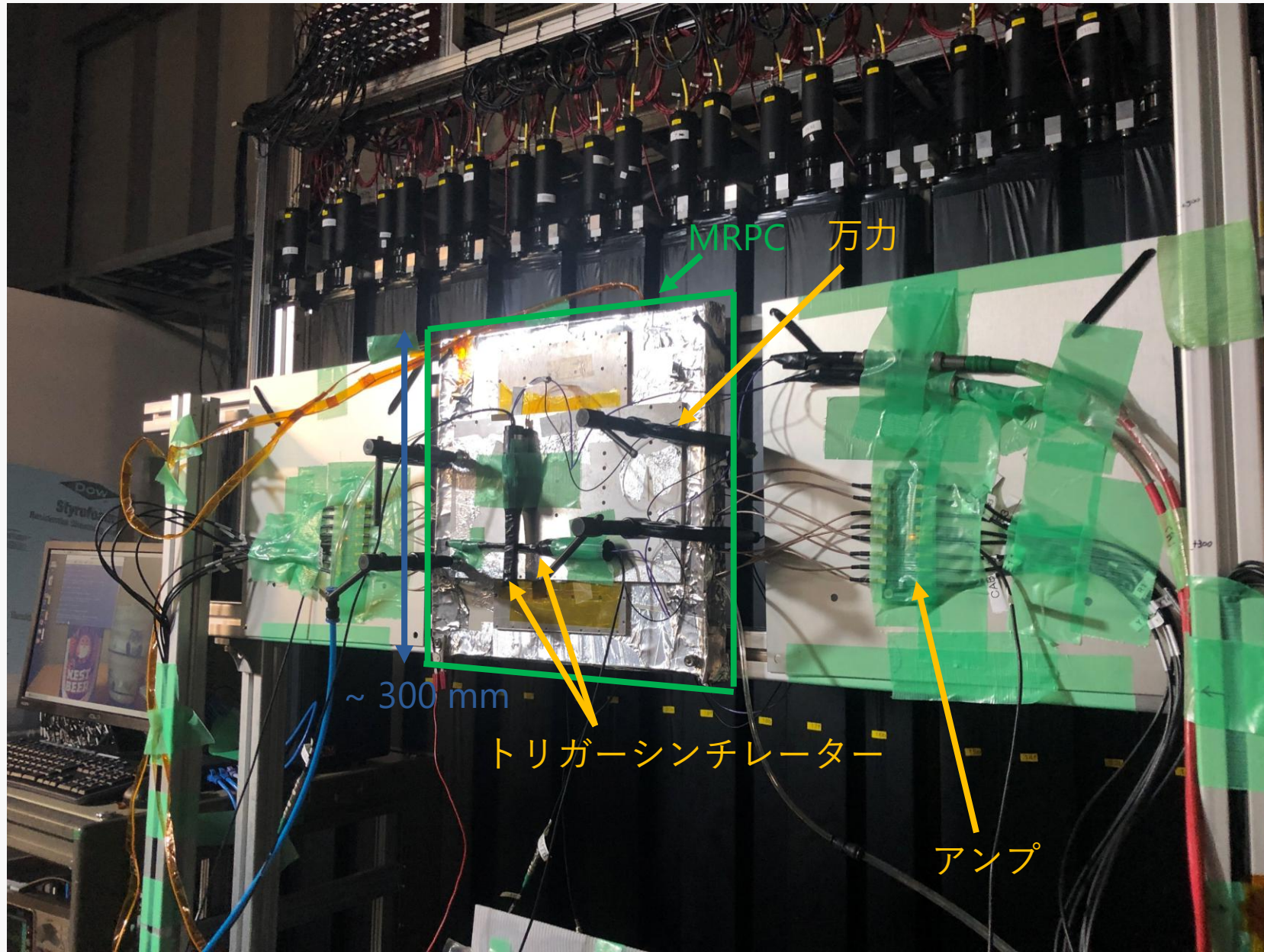






図 4.6: ポリエステルフィルムスペーサーの構造。市販のフィルムやテープを組み合わせている。